



Understanding the Damage and Microstructural Evolution in Cu Metallizations during Thermo-mechanical Fatigue

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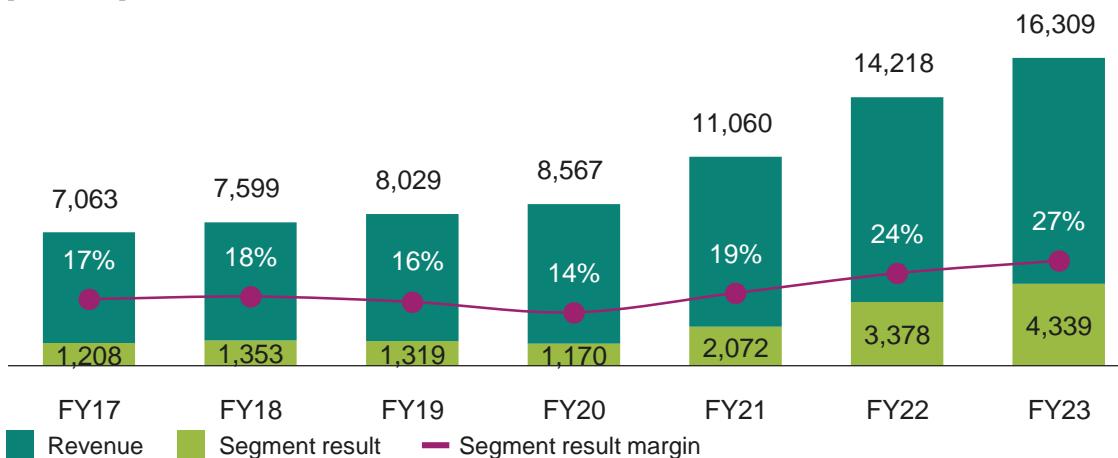
Infineon at a glance

Growth areas



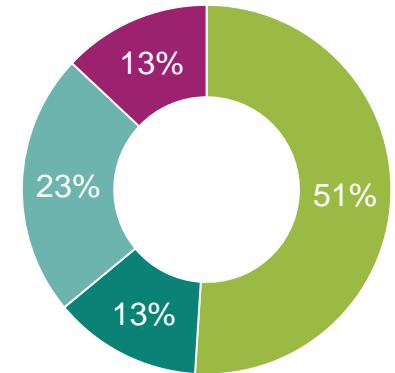
Financials

[EUR m]



FY23 revenue by segment¹

- Automotive (ATV)
- Green Industrial Power (GIP)
- Power & Sensor Systems (PSS)
- Connected Secure Systems (CSS)

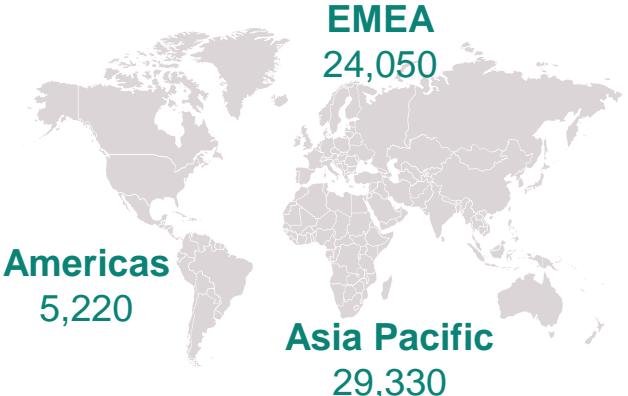


Employees²

58,600
employees worldwide

69
R&D and

17
manufacturing locations²



For further information: [Infineon Annual Report](#).

¹ 2023 Fiscal year (as of 30 September 2023) | ² As of 30 September 2023



Motivation

- Materials integration and development for the next generation of power semiconductor technologies
- Digitalization and electrification of our society and its supply with sustainable energy
- European Green Deal for climate neutrality by 2050



Project objectives

- Develop a defect characterization workflow using advanced X-ray and electronprobe related techniques
- Modelling approaches to new wide bandgap power semiconductor materials and 3D integrated power technologies
- Using FAIR (findable, accessible, interoperable and reusable) data principles required for digitalization and industry 4.0

Outline

- Challenges in power electronic application
- Thermo-mechanical fatigue testing & modeling
- 3D characterization of damage networks



10/11 partners in 5 countries

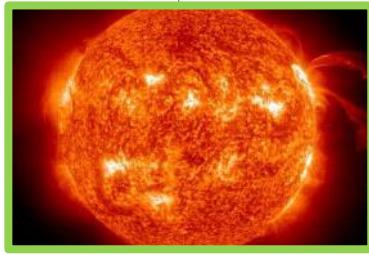
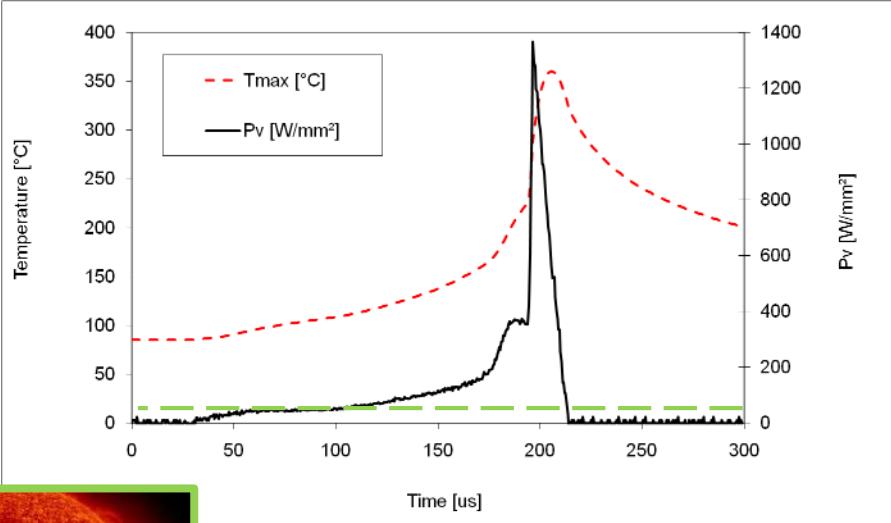
Challenges in power electronic applications

Thermo-mechanical fatigue



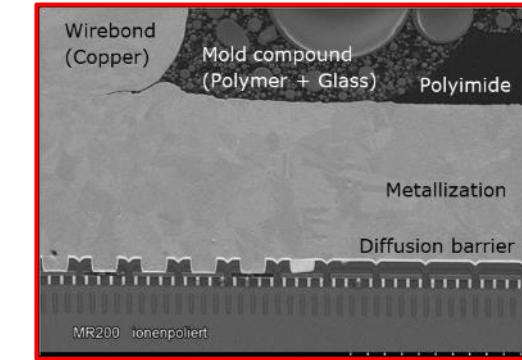
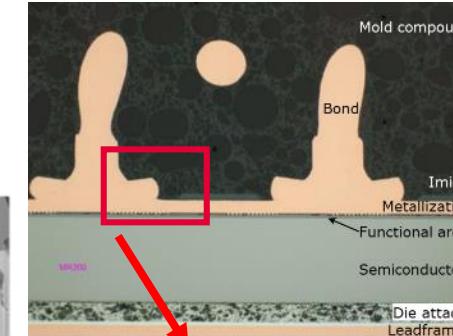
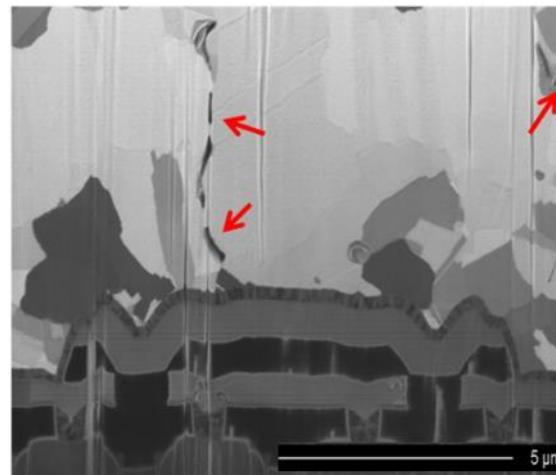
In power electronic applications, malfunction and short circuit events cause high overload pulses, leading to rapid heating up to high temperatures.

Typical overload pulse in a power electronic device



surface of the sun: 63 W/mm²

After thermo-mechanical cycling [2]



Structure of a power electronic device [1]

Degradation of the metallization layer due to multiple overload pulses and final device failure.

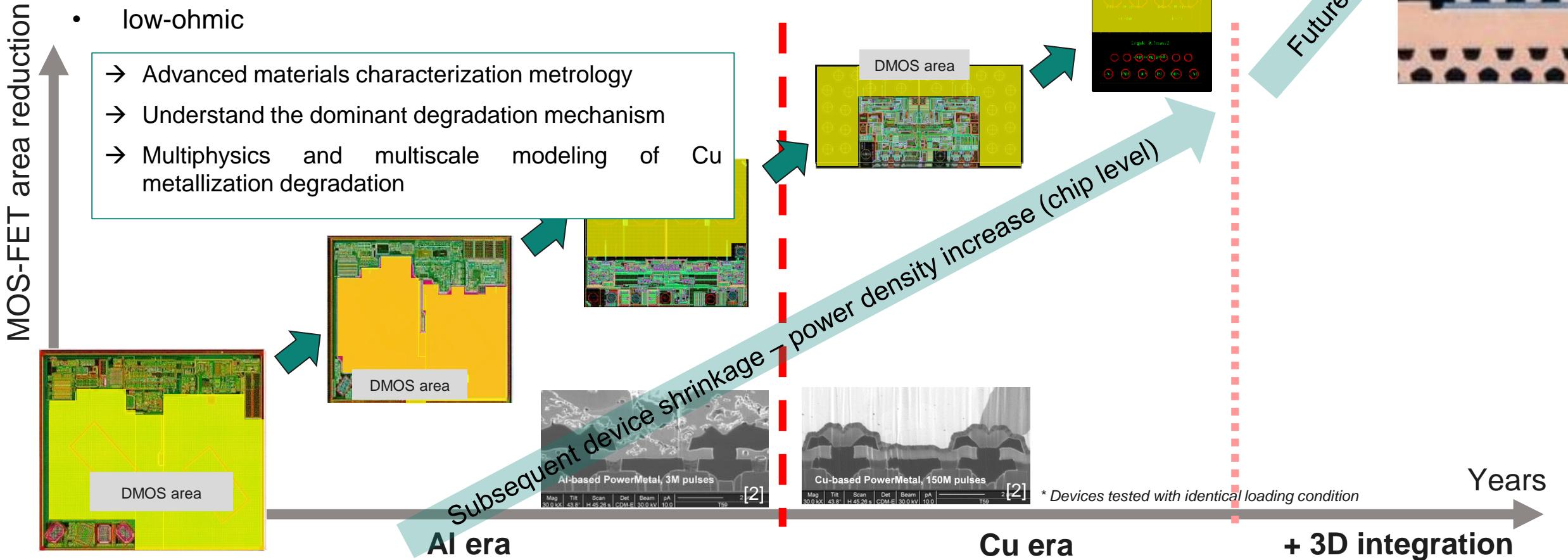
Challenges in power electronic applications

Thick Cu as enabler for aggressive device shrink

30 years of shrinkage in subsequent generations in „automotive high-side smart power switch“

Example: Power electronic switches for 12V board net

- self-protecting (temperature, current, voltage) to guarantee reliable functioning
- low-ohmic



Thermo-mechanical fatigue testing + modeling

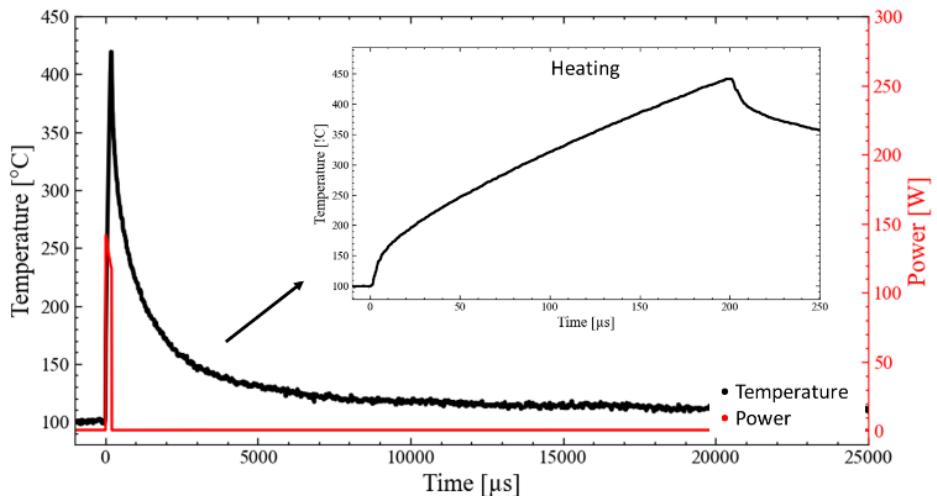
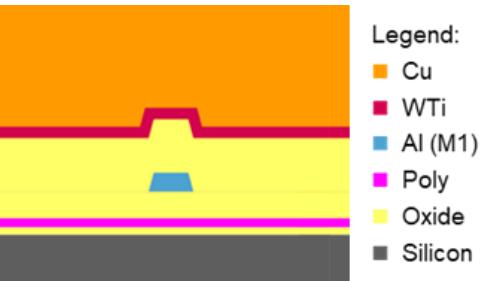
Polyheater test structures

Test chip to investigate the thermo-mechanical degradation of power electronic metallization layers via repetitive fast heat pulsing

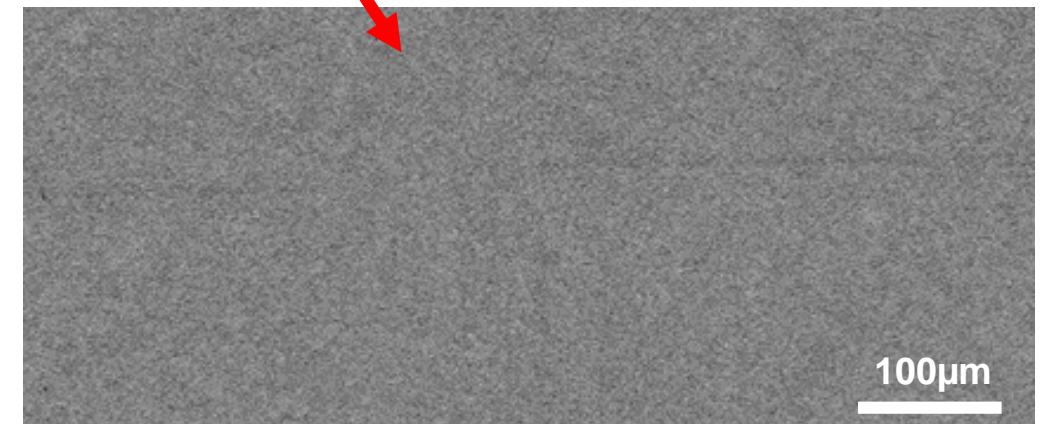
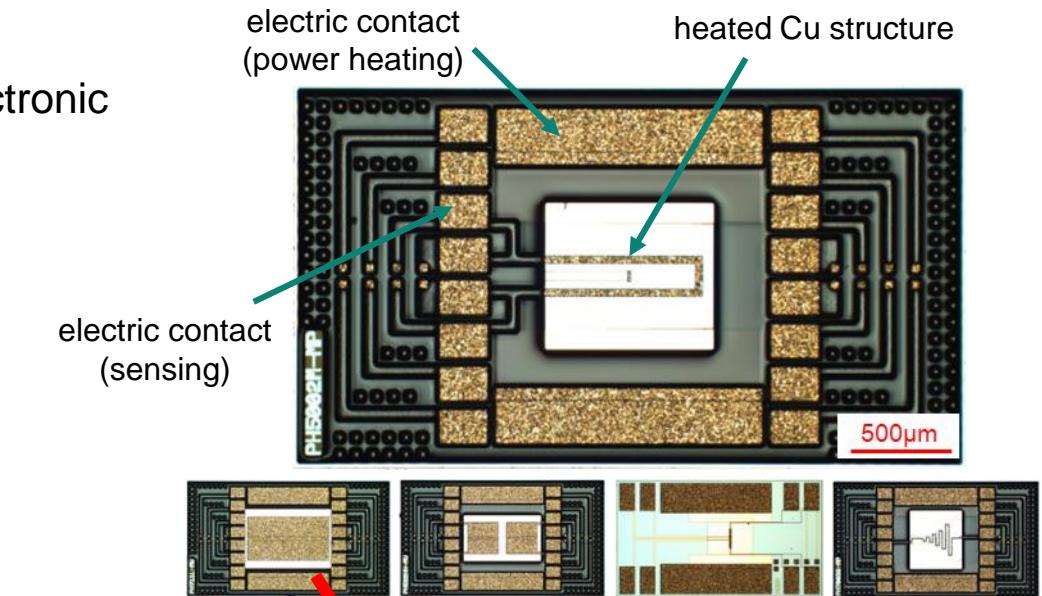
Test Parameters which can be varied:

- T_{Base} (RT - 150 °C)
- T_{Max} (up to 650 °C)
- Pulse Length (200 μ s (*) – 20ms)
- Ambient: Air, Vacuum, Forming gas
- Repetition rate: 5 pulses/sec - ...

(*) Heating rate of $\sim 1.5 \times 10^6$ K/sec ($\Delta T = 300^\circ\text{C}$)



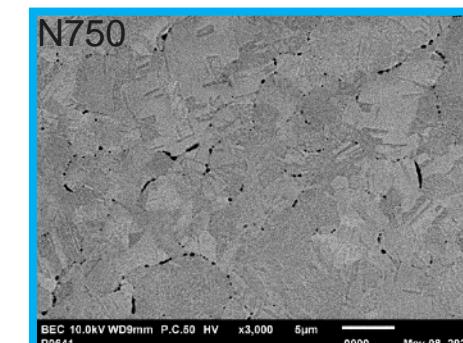
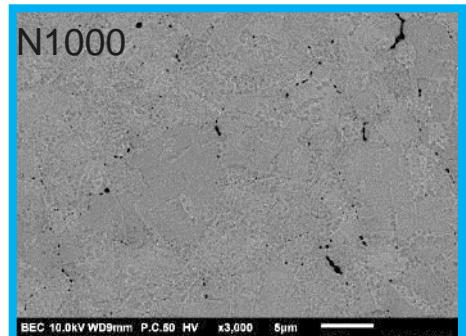
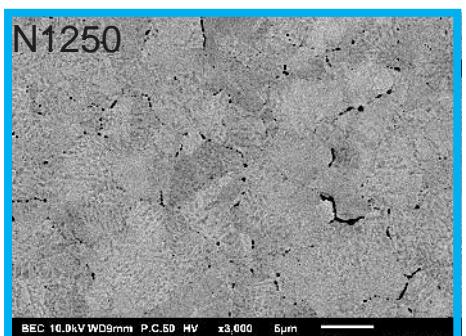
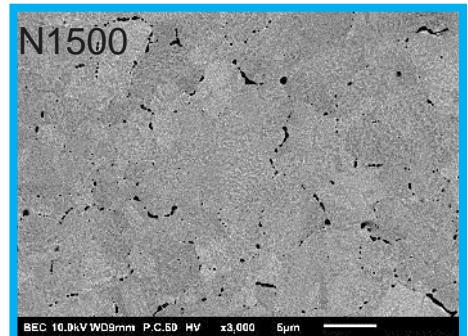
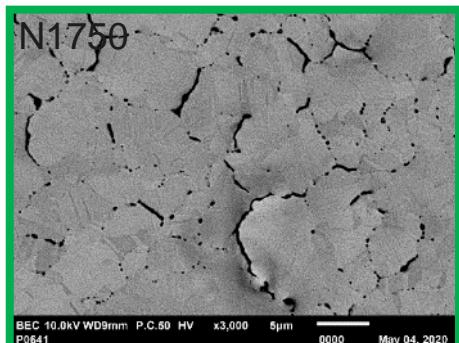
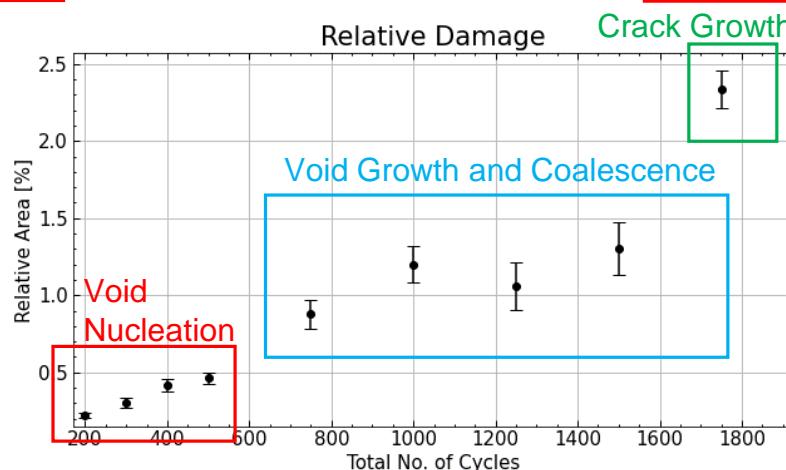
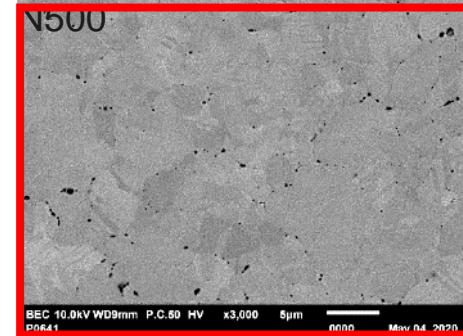
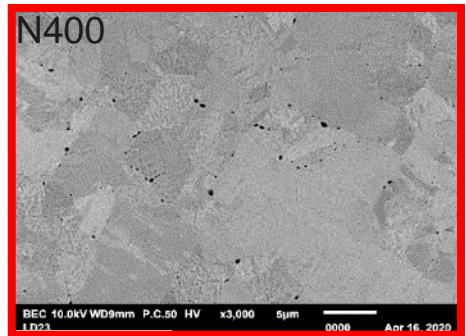
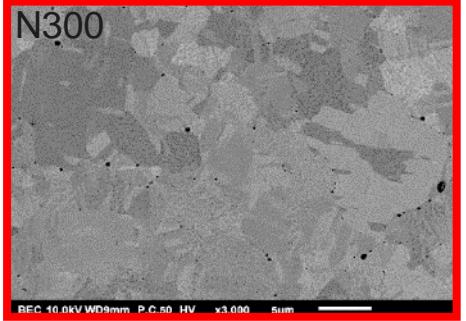
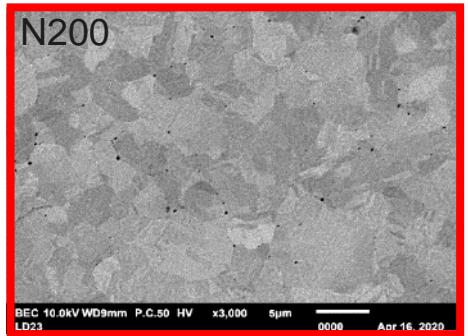
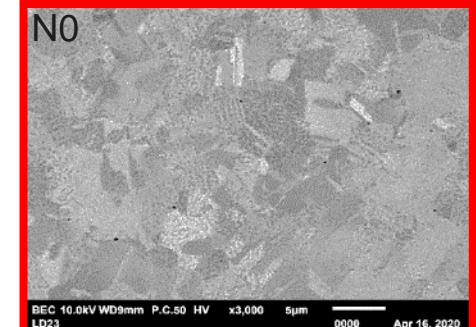
50000 cycles



In-situ experiment showing the damage evolution on the Cu surface

Thermo-mechanical fatigue testing + modeling

Post-testing 2D Scanning electron microscopy study



Applied test conditions:

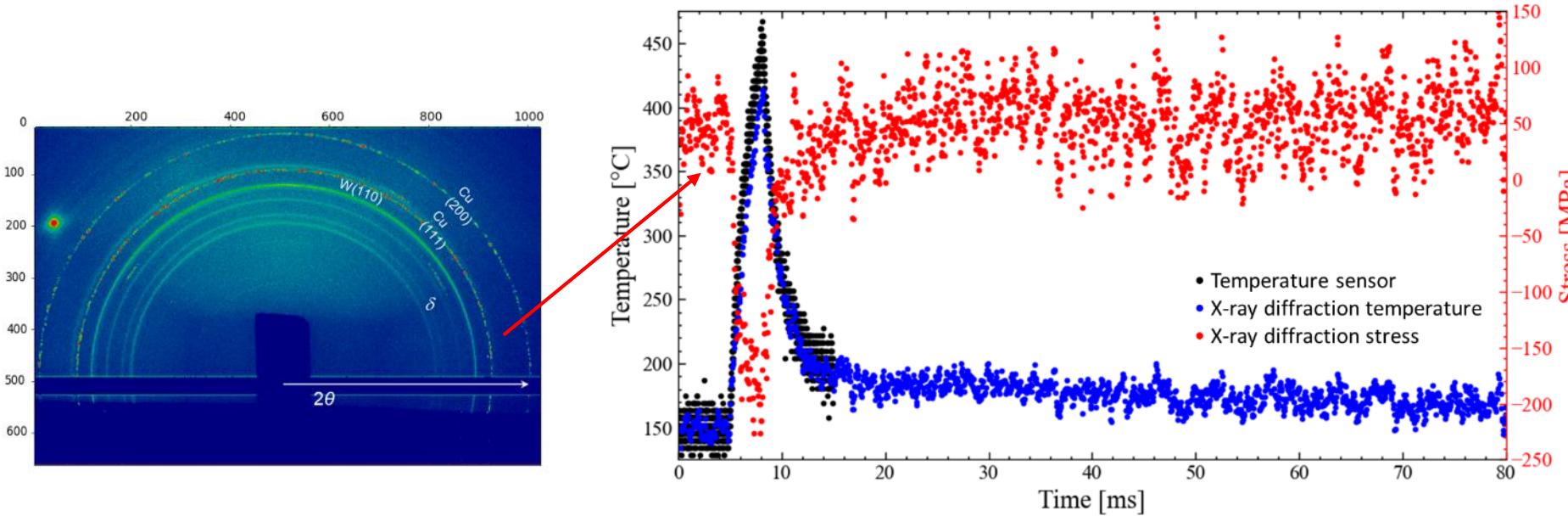
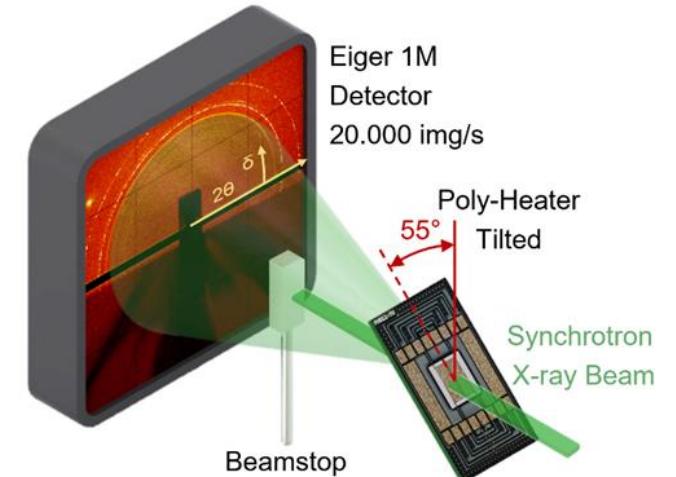
- $T_{\text{base}}: 100 \text{ }^{\circ}\text{C} - T_{\text{max}}: 400 \text{ }^{\circ}\text{C}$
- Pulse Length: 200 μs
- Repetition rate: 1 Pulse/sec

Thermo-mechanical fatigue testing + modeling

Thermo-mechanical stress in metallization layers

Ultra-fast 20 kHz X-ray diffraction (Synchrotron: PSI - MS-Powder)

- In-situ time resolved X-ray diffraction to determine the stress within Cu metallization with 20.000 fps (every 50 μ s)
- Acquisition of diffraction patterns (DP) allows to determine temperature and thermo-mechanical stress throughout the course of a single heating pulse

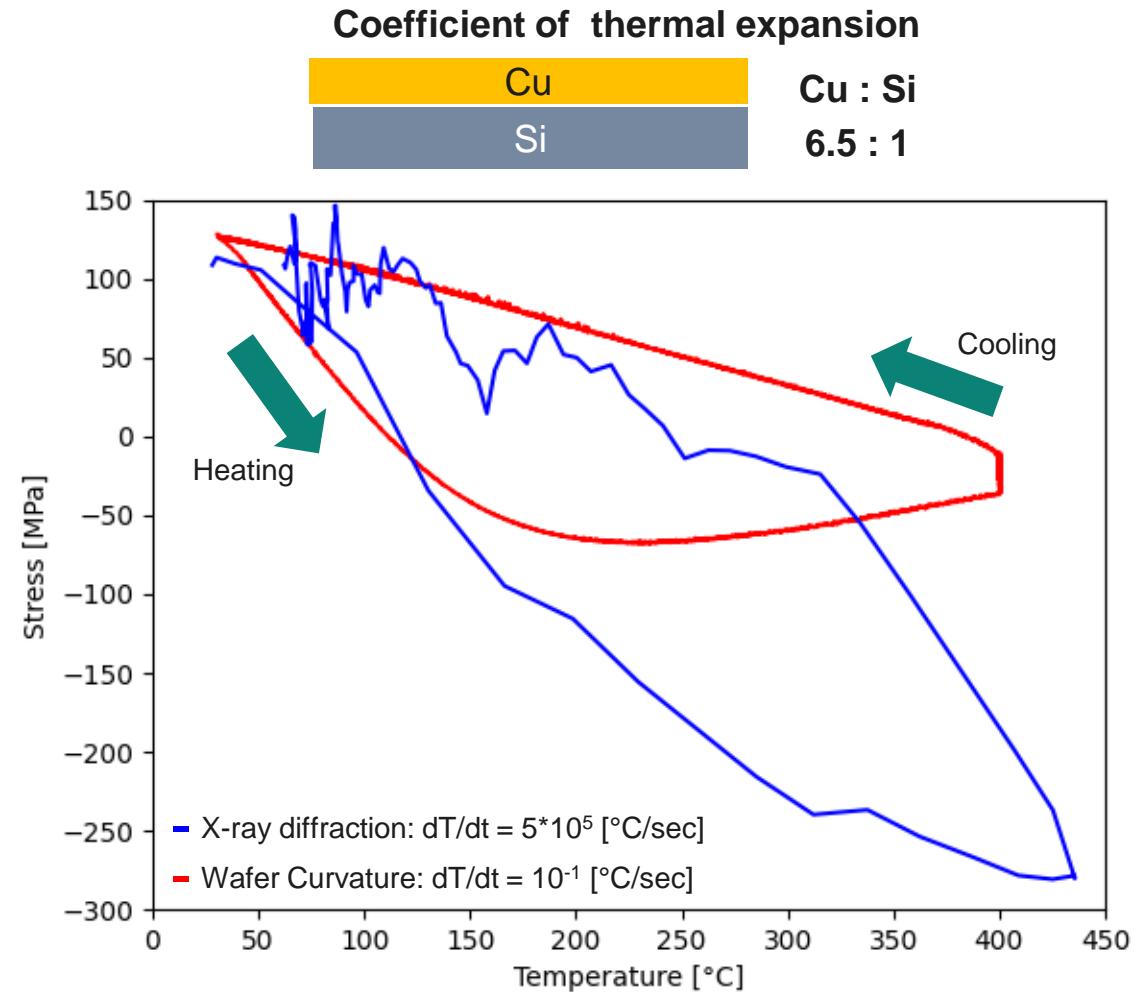


Applied test conditions:

- $T_{\text{base}}: 150 \text{ }^{\circ}\text{C}$ - $T_{\text{max}}: 400 \text{ }^{\circ}\text{C}$
- Pulse Length: 3200 μ s

Slow heating vs. rapid heating

- Different deformation mechanisms are activated in high strain rate regime
- High thermo-mechanical stresses were measured but data evaluation is challenging
- Slow heating experiments (e.g.: Wafer Curvature) are not representative for application-relevant stresses

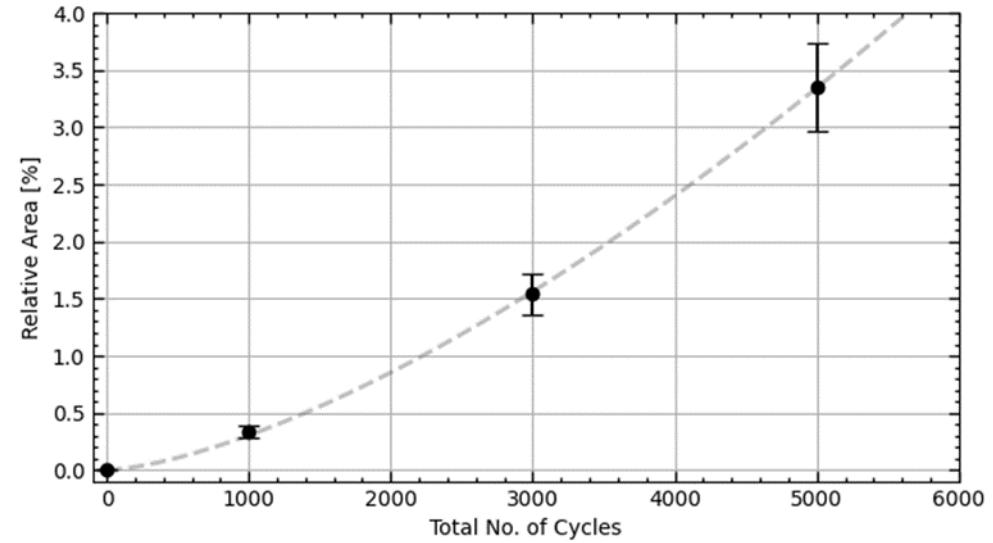
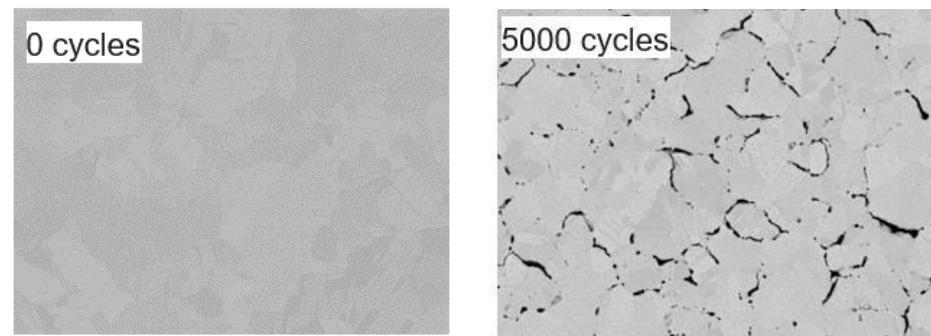
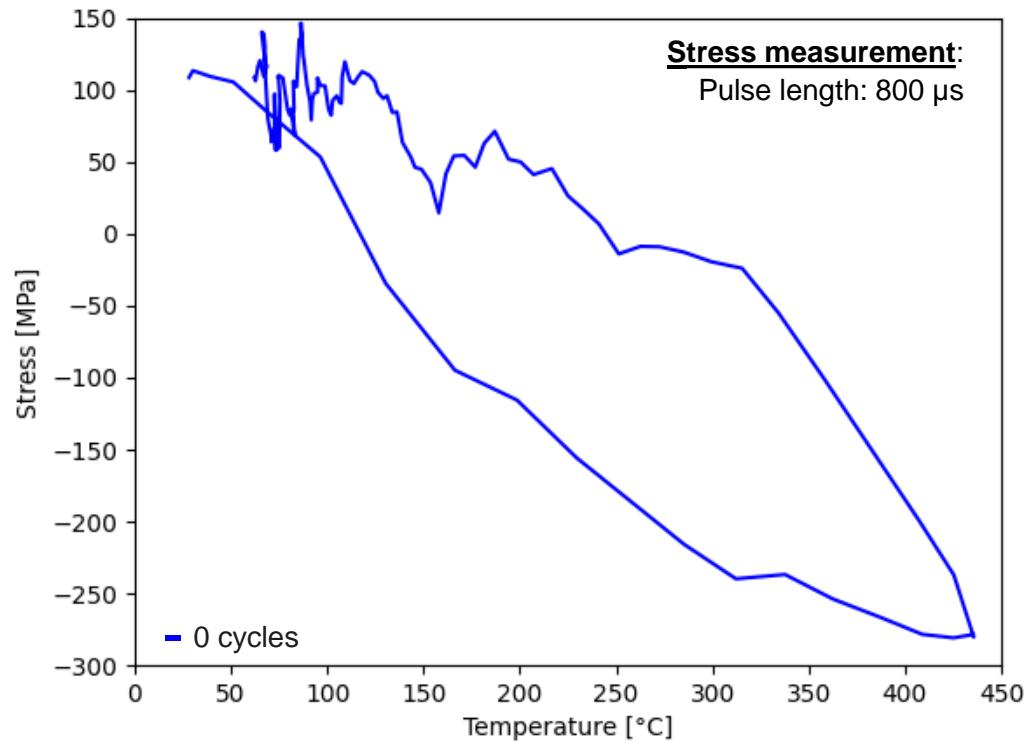


Evolution of the thermo-mechanical stress in a 20 μm Cu metallization through the course of a heat cycle

Thermo-mechanical fatigue testing + modeling

Thermo-mechanical stress in metallization layers

Thermo-mechanical stress evolution:



The damage formation leads to a cyclic softening in the metallization layer and a decrease of total thermo-mechanical stress.

TMF cycling:

- $T_{\text{base}}: 100 \text{ }^{\circ}\text{C} - T_{\text{max}}: 400 \text{ }^{\circ}\text{C}$
- Pulse Length: 200 μ s
- Repetition rate: 1 Pulse/sec

Thermo-mechanical fatigue testing + modeling

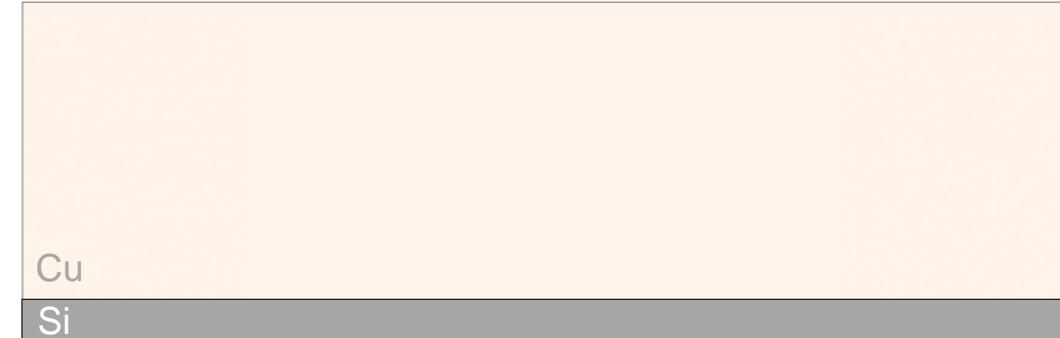
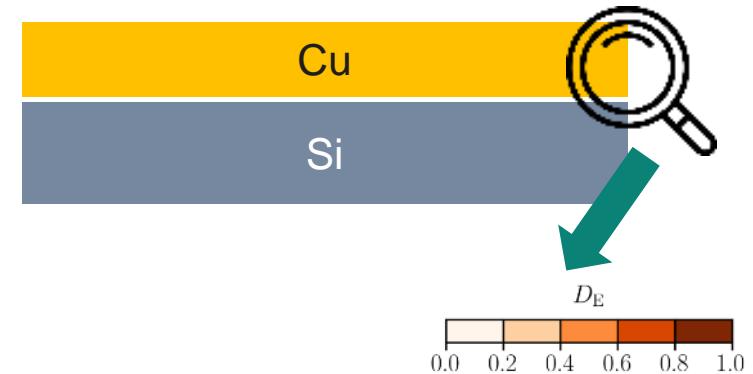
2D Modeling based on SEM imaging

Today: 2D Damage Modelling

- SEM imaging to determine weak spots in microstructure
- Input for 2D FEM-based damage modeling
- Calibration based on Top view and Cross-Section view SEM images



Initial distribution of the damage onset variable D_0 [1]



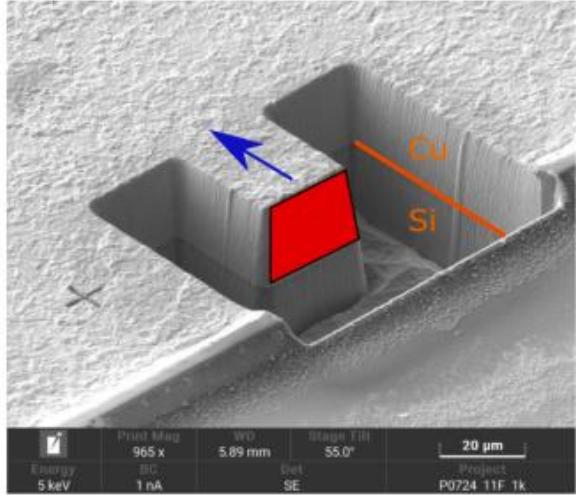
Evolution of the damage variable D_e during cycling [1]

Future: 3D Modelling

- To consider complex 3D integrated structures for damage model
- 3D characterization techniques to study the damage network formation

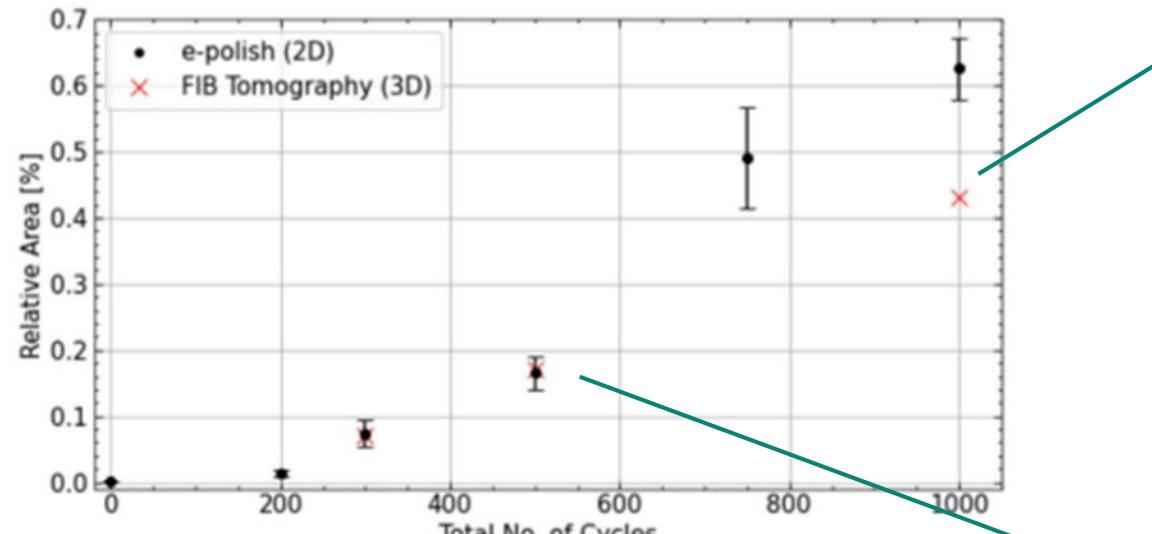
3D characterization of damage networks

FIB Tomography – Comparison of 2D and 3D

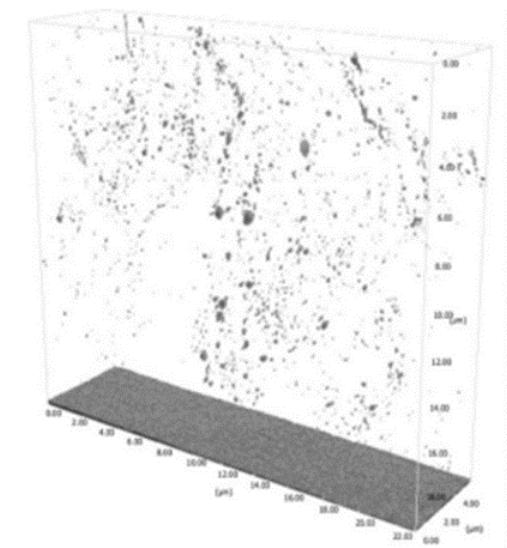
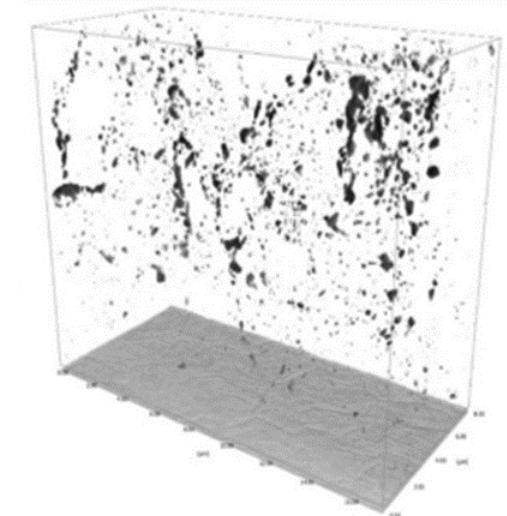


Laboratory FIB Tomography

- Voxel Volume: $30 \times 30 \times 30 \text{ nm}^3$
- SE and FIB images were recorded
- Enhanced information for void/crack detection and quantification



- Damage network revealed in laboratory and good correlation between 2D and 3D data
- Very time consuming and destructive

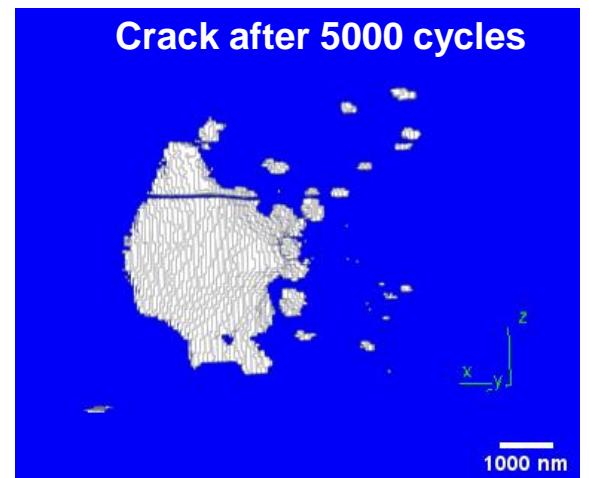
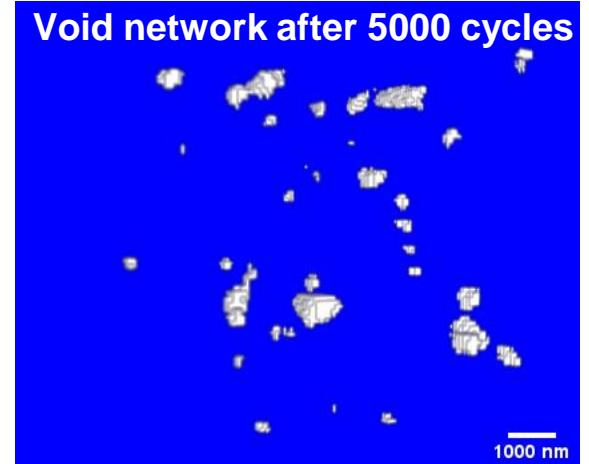
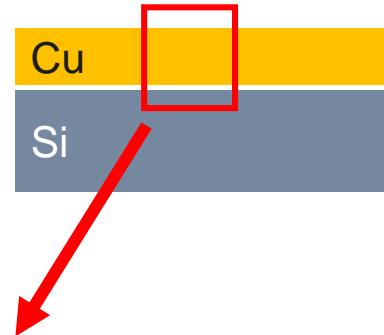
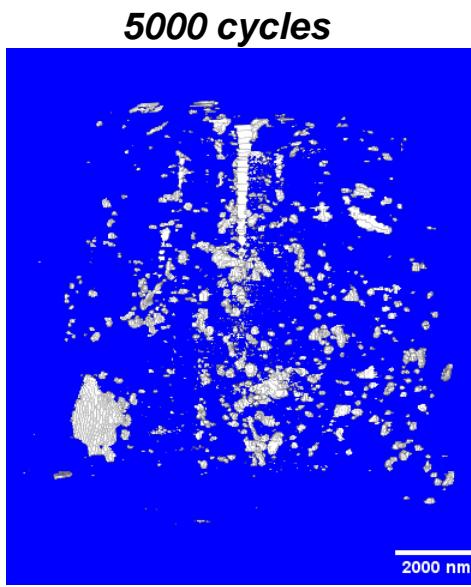
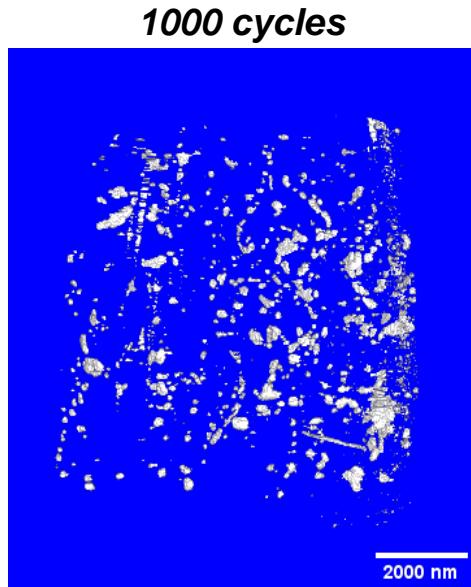
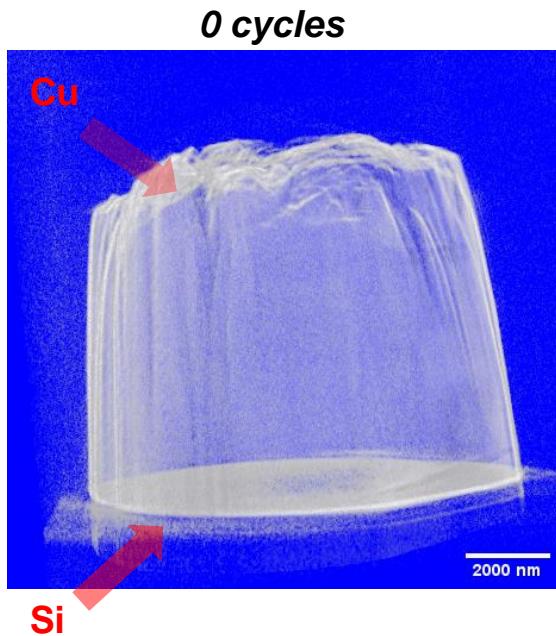


3D characterization of damage networks

Nano-Tomography – Preparation artefact-free ground truth

Synchrotron: Tomography (DESY P05)

- Post testing characterization of the resulting damage network
- Voxel volume: $14.8 \times 14.8 \times 14.8 \text{ nm}^3$
- 3D damage network and alignment of vertical features
- Continuous increase of damaged volume

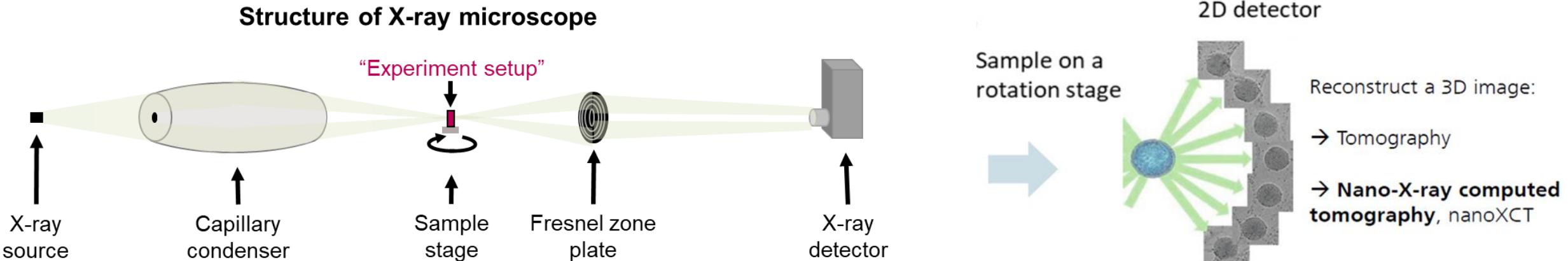


Applied test conditions:

- $T_{\text{base}}: 100 \text{ }^{\circ}\text{C} - T_{\text{max}}: 400 \text{ }^{\circ}\text{C}$
- Pulse Length: 200 μs
- Repetition rate: 1 Pulse/sec

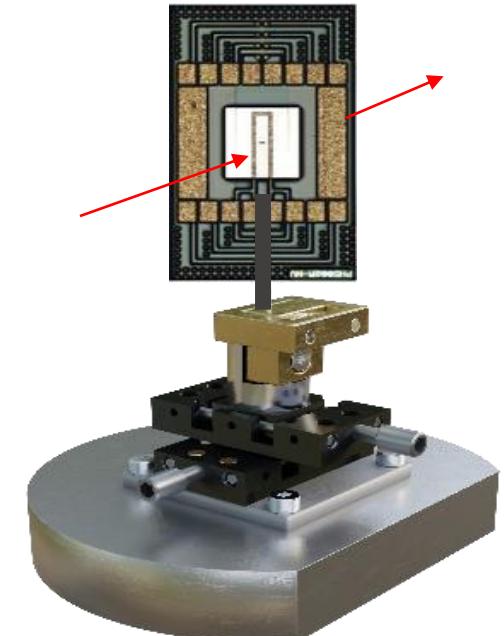
3D characterization of damage networks

Lab X-ray microscopy – Introduction



Optical beam path of state-of-the-art TXM/nano-CT tool

- Varying X-ray absorption inside sample results in 2D-radiographies
- Sample mounted on a rotating stage
 - Rotates inside the beam to allow complete view of sample
- Only 180° rotation necessary because of the nearly parallel-beam geometry
 - Nondestructive 3D-imaging technique
 - Preparation artefact free volume information



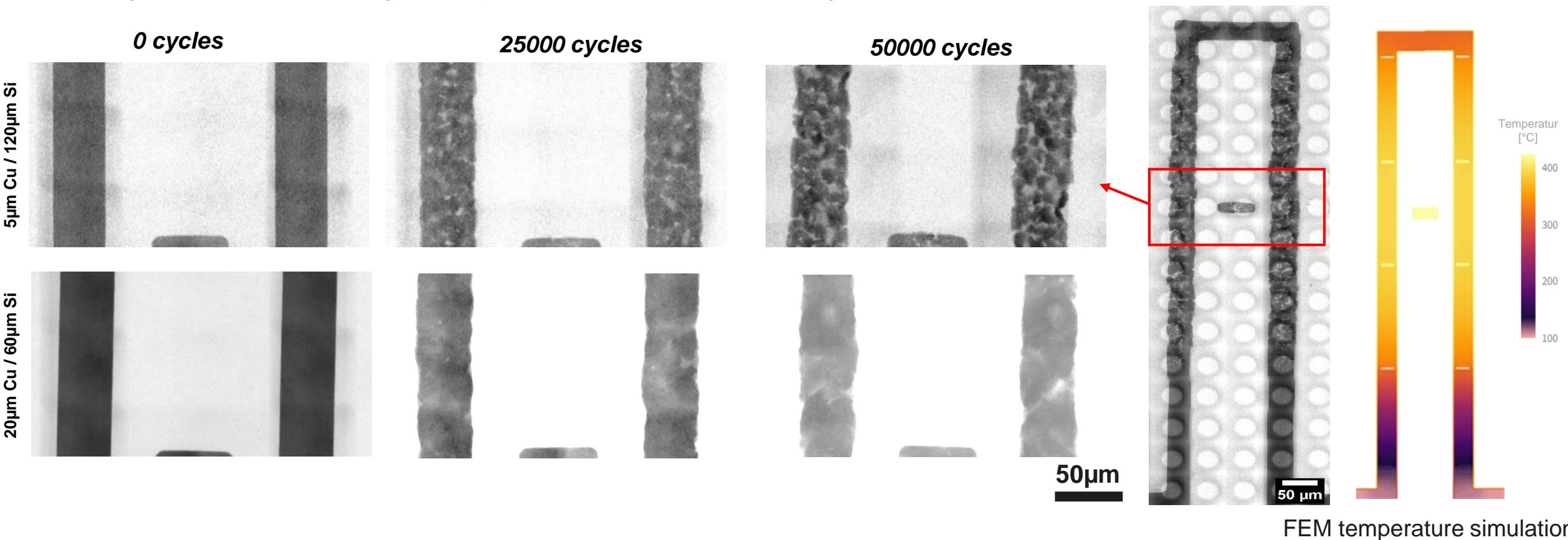
3D characterization of damage networks

Radiography to reveal damage evolution

- Radiography mapping after different cycling states: 126 single mosaic images with 65 μ m FoV
- Spatial damage distribution correlates well with temperature
- Degradation details are missing due to projection view
- Radiographs of the sample geometry with thinner copper providing more detailed information

Applied test conditions:

- T_{base} : 100 °C - T_{max} : 400 °C
- Pulse Length: 200 μ s
- Repitition rate: 1 Pulse/sec

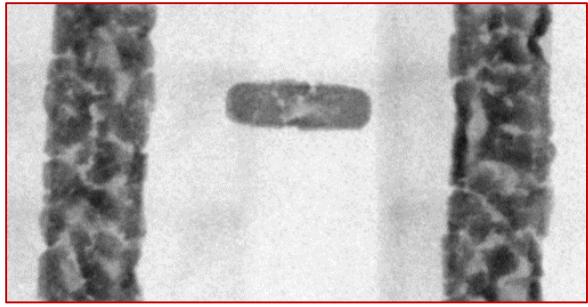
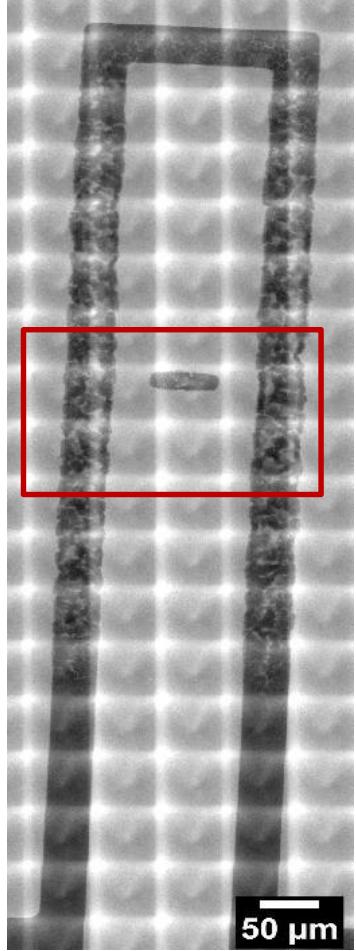


3D characterization of damage networks

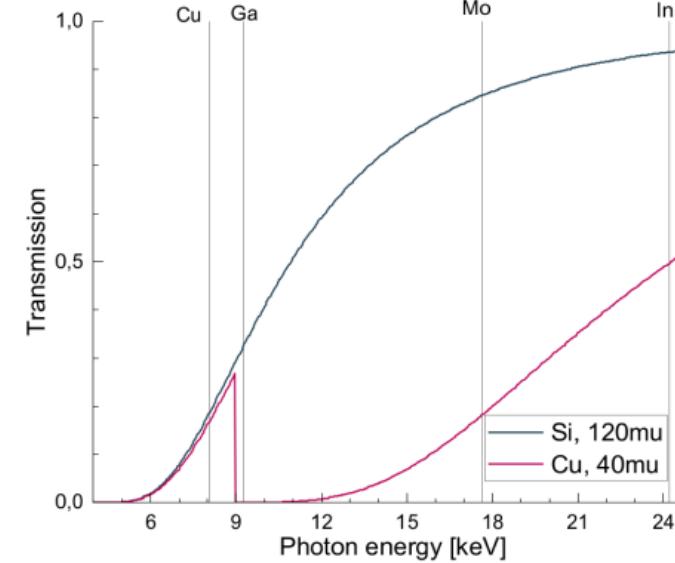
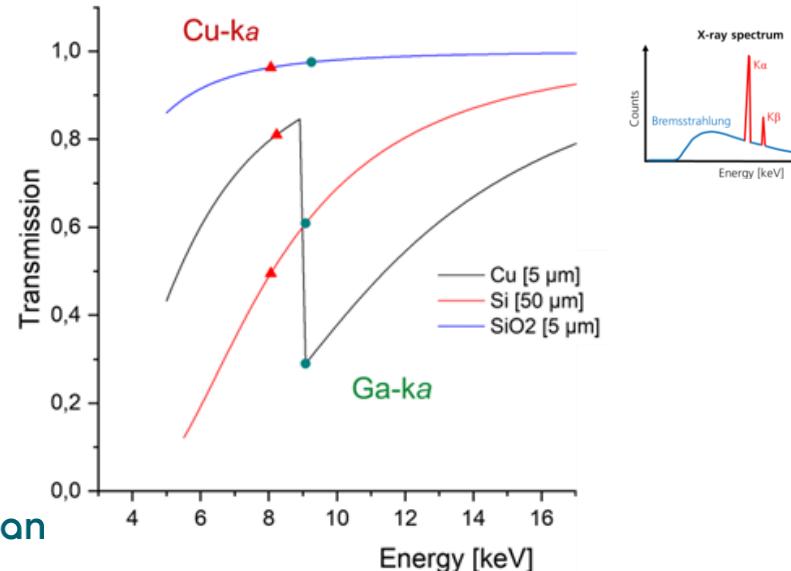
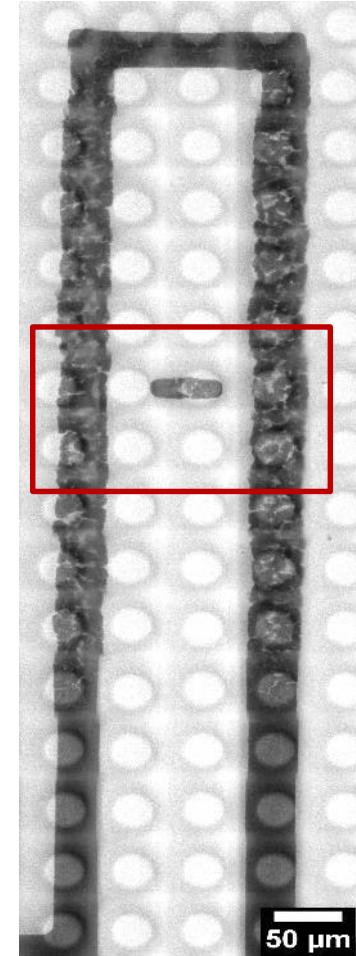
Radiography using multi-photon energies (Cu-K α , Ga-K α) on 5 μ m Cu

Cu-K α (8.05 keV)

- Innovative liquid metal-jet X-ray source technology (Ga-K α) with 9.05 keV provides enhanced contrast for Cu structures in dielectrics
- Use high energetic source such as In to enable the characterization of thick Cu structures

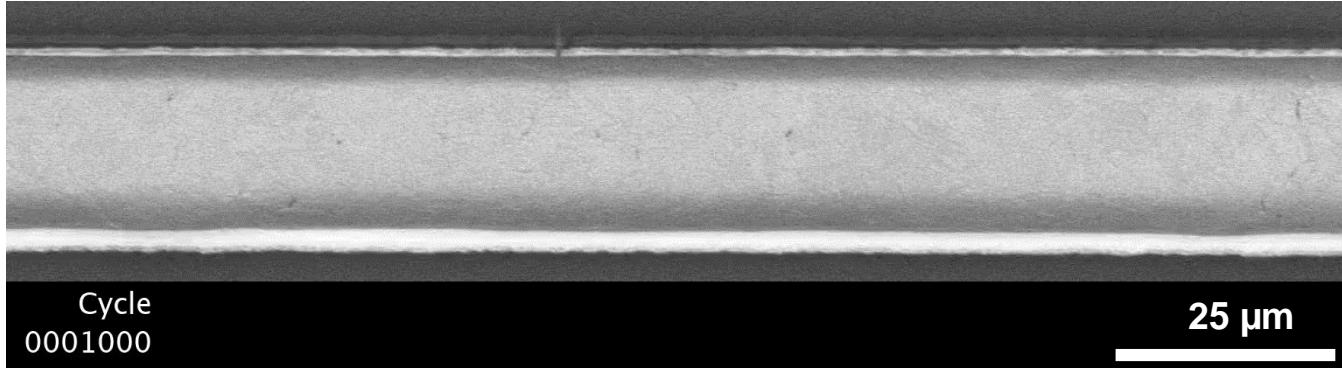


Ga-K α (9.25 keV)



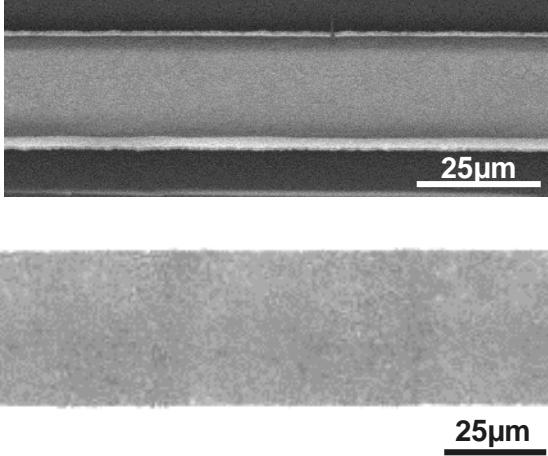
3D characterization of damage networks

Radiography vs. in-Situ SEM

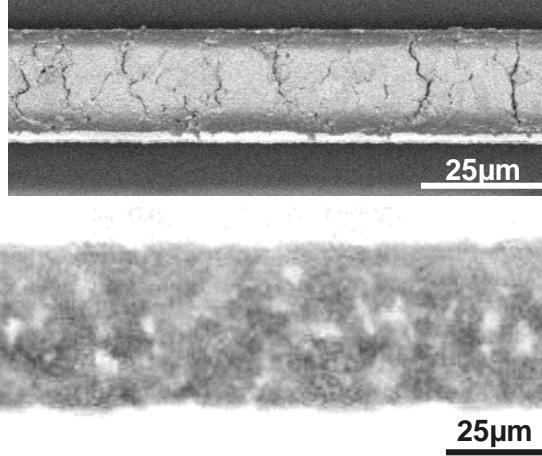


0 cycles

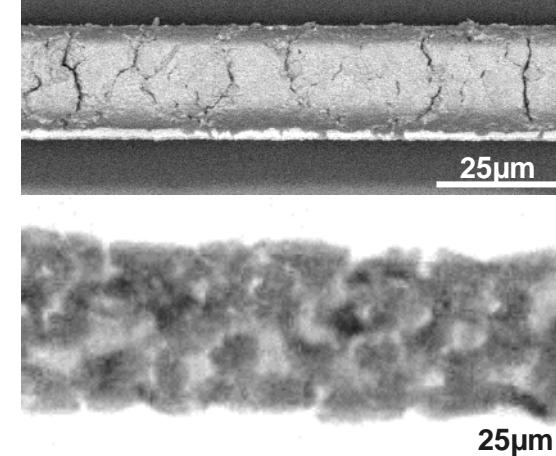
SEM



25000 cycles



50000 cycles



Radiography



25μm

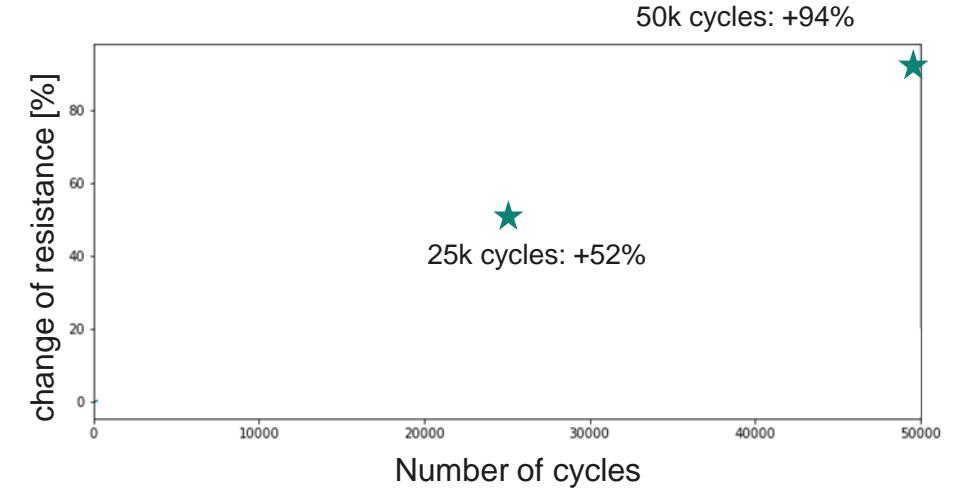


25μm



25μm

change of resistance [%]



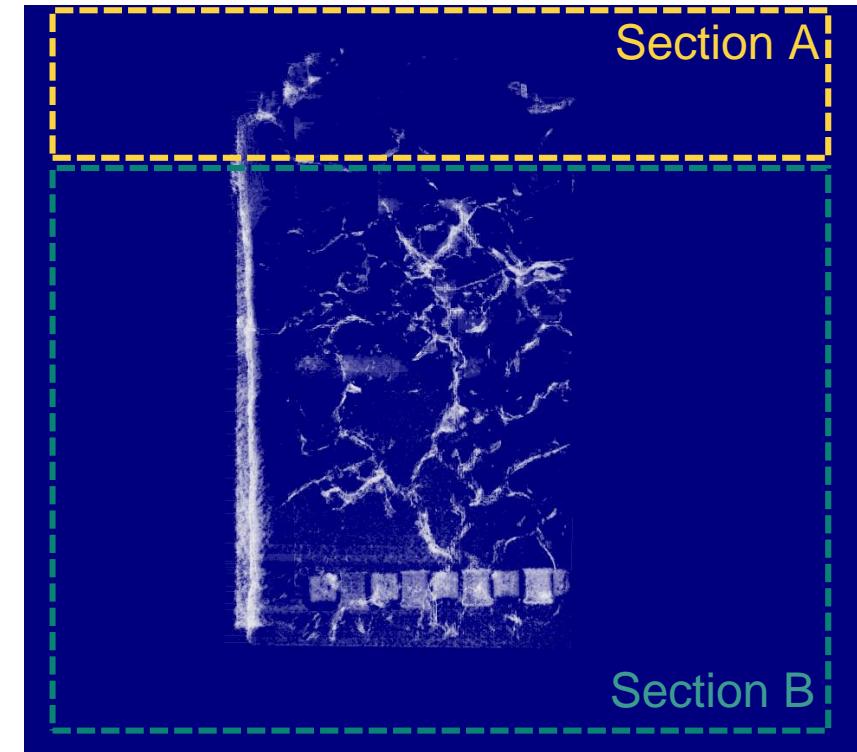
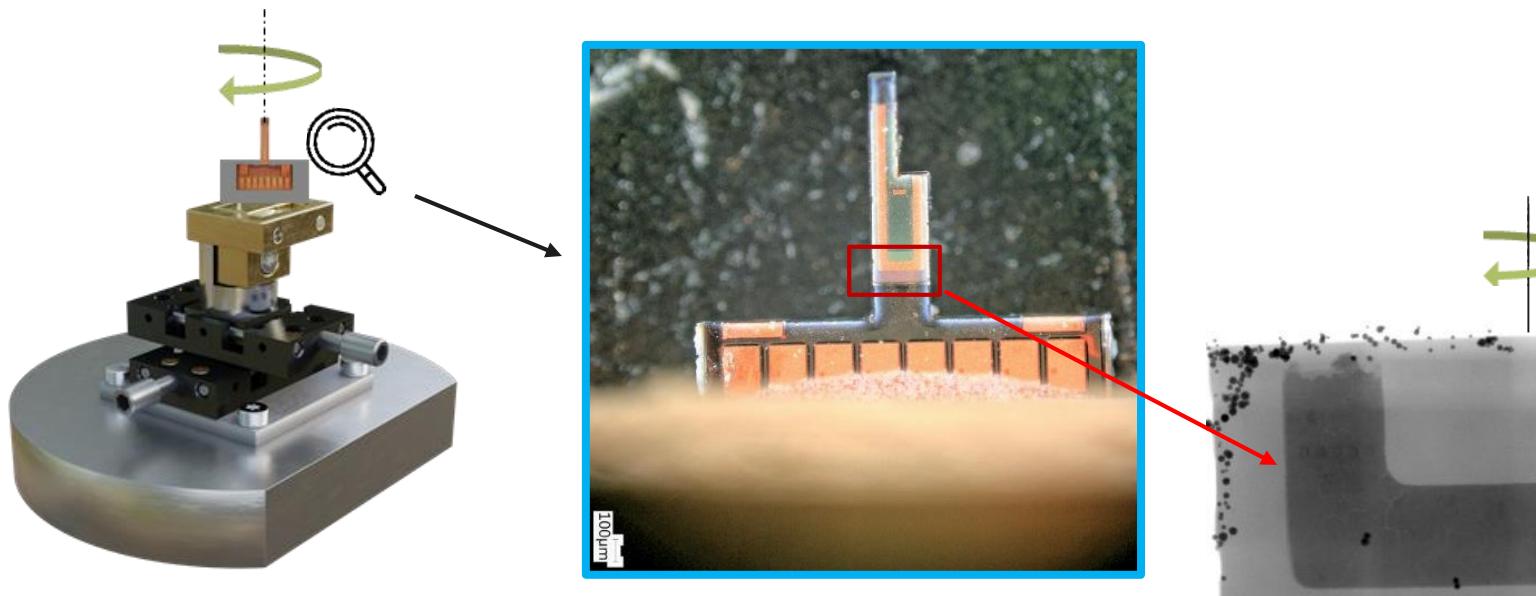
Applied test conditions:

- T_{base} : 100 °C - T_{max} : 400 °C
- Pulse Length: 200 μs
- Repitition rate: 1 Pulse/sec

3D characterization of damage networks

Lab X-ray tomography of realistic test structure

- Modified sample geometry enables a section for a tomography with an angular range of 180°
- Two sections within on sample:
 - Section A: Single line
 - Section B: 2 parallel lines with limited transparency
- Smearing effect leads to damage overestimation
- Tomography on „real structures“ requires higher energetic X-ray source and the corresponding optics

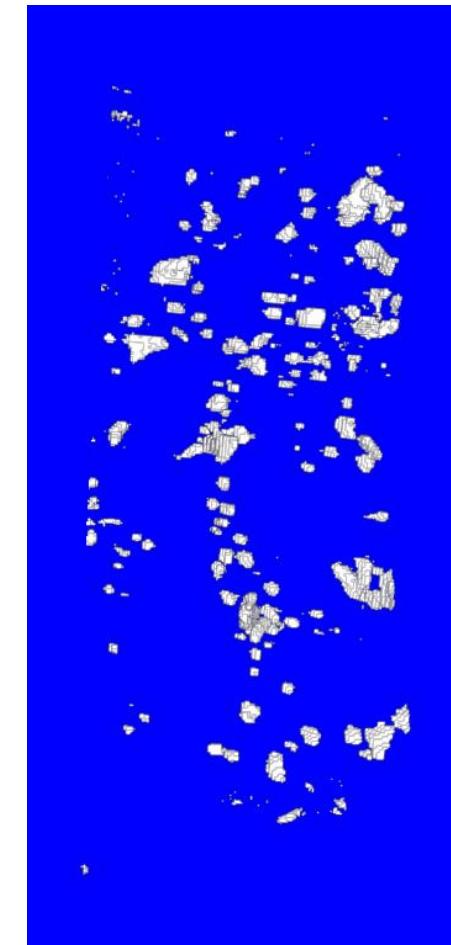


Applied test conditions:

- T_{base} : 100 °C - T_{max} : 400 °C
- Pulse Length: 200 μ s
- Repetition rate: 1 Pulse/sec
- 25000 cycles

Conclusion

- **Thermo-mechanical fatigue leads to the formation of complex 3D damage networks.**
 - Void nucleation → Void growth and coalescence → Crack growth
 - Grain boundaries and triple junctions are weak spots
 - Vertical alignment of damage features identified by 3D techniques
 - Radiography reveals damage progression within the volume after surface damage saturation.
- **Large thermal stresses due to high heating rates and cyclic softening due to degradation**
 - Dedicated test structures are required to achieve application relevant conditions
 - In-Situ experiments necessary to monitor evolution
- **Lab X-ray microscopy has a high potential for damage monitoring in semiconductor industry**
 - Using In-K α radiation (24 keV) and Ga-K α (9.2 keV) radiation X-ray sources
 - Non-destructive investigation of thick metallization's or complex 3D integrated structures
 - Enhanced contrast and detailed information
 - New test structures design for in-situ X-ray microscopy and in-situ damage monitoring
 - Advanced damage segmentation algorithms are required for quantification of 3D data
 - Input for predictive 3D damage modeling



Lab X-ray microscopy is a key characterization method to enable the 3D integration of future power electronic technologies!

Thank you for your attention!

Questions?

Acknowledgment:

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Paul Scherrer Institute – S. van Petegem

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